



Session Title:	[TE3] EUV HVM Status and Cutting-Edge Topics in Advanced Lithography
Session Date:	November 21 (Tue.), 2023
Session Time:	14:25-16:10
Session Room:	Room E (Sidney Room, 2F)
Session Chair:	Prof. Jong-Rak Park (Chosun Univ., Korea)

[TE3-1] [Plenary] 14:25-15:10

EUV Systems for High Volume Manufacturing

Stuart Young (ASML Netherlands B.V., The Netherlands)

[TE3-2] [Invited] 15:10-15:40

Deciphering Line Edge Roughness Formation in EUV Patterning: Insights from Molecular Simulations and Strategies for Minimization

Su-Mi Hur (Chonnam Nat'l Univ., Korea)

[TE3-3] [Invited] 15:40-16:10

Thermal Emission Steering and Mid-IR Complex Amplitude Modulation with Graphene-Based Active Metasurfaces

Min Seok Jang (KAIST, Korea)